



# **Characterization of SC CVD diamond detectors for heavy ions spectroscopy and MIPs timing**

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## ABOUT SAMPLES



SC CVD diamonds → producer e6

SC-E6-4 → 3.5 x 3.5 x 0.48 mm<sup>3</sup>; Cr(50 nm) Au (100 nm)

BDS-5 → 5 x 5 x 0.325 mm<sup>3</sup>; Cr(50 nm) Au (100 nm)

BDS 7 → 5 x 5 x 0.318 mm<sup>3</sup>; Cr(50 nm) Au (100 nm)

BDS 9 → 5 x 5 x 0.32 mm<sup>3</sup>; Al(100nm) guard ring

BDS 10 → 5 x 5 x 0.3 mm<sup>3</sup>; Al(100nm) guard ring

BDS 14 → 5 x 5 x 0.49 mm<sup>3</sup>; Al(100nm) guard ring

### **Cleaning and oxidation before metallisation:**

If metallised before → Aqua Regia

H<sub>2</sub>SO<sub>4</sub> + KNO<sub>3</sub> boiling ~30 min → rinse with ultra-pure water ultrasonic bath → dry with N<sub>2</sub>

**Metallisation sputtering or evaporation at Target Laboratory of GSI → Bettina Lommel talk**

Cr(50nm)Au(100nm) ; Ti(30nm)Pt(50nm)Au(100nm); Al(100 nm) → **annealing 500C for 10min**  
**Ar**

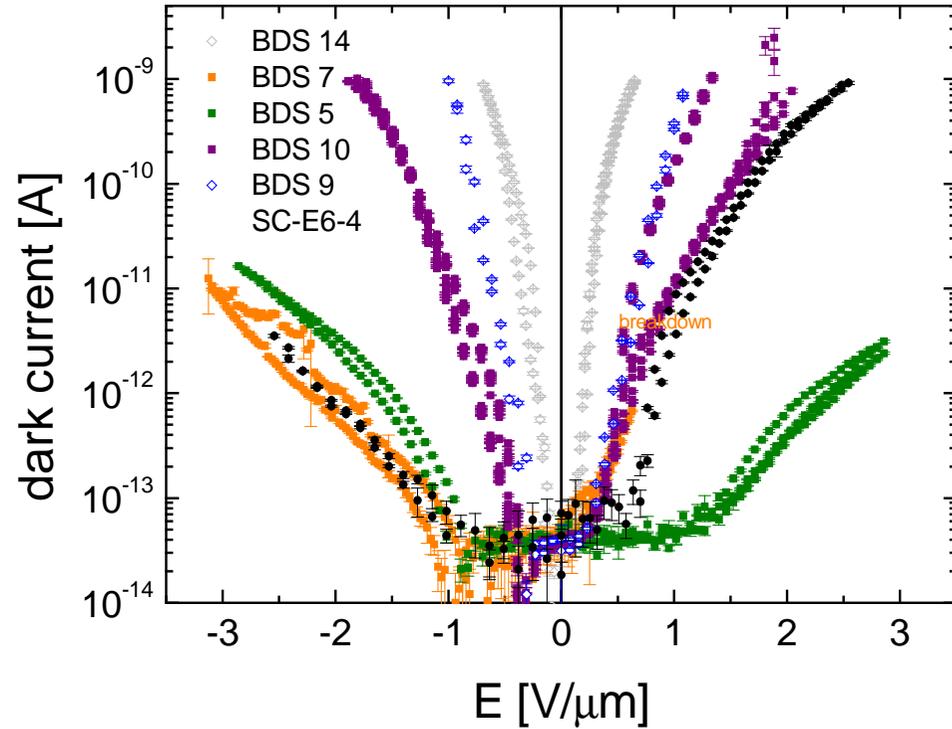


## OUTLINE



- Current-Voltage characteristics and surfaces influence
- Charge collection properties and stability
- Energy resolution
- Timing properties
- Summary

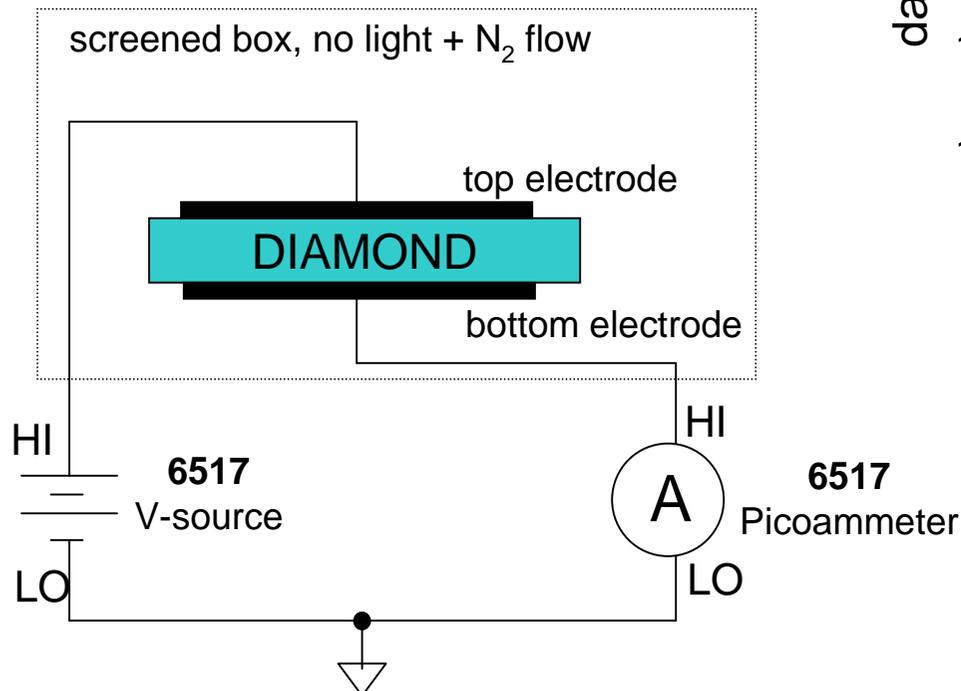
## „Zoo” of I-V characteristics

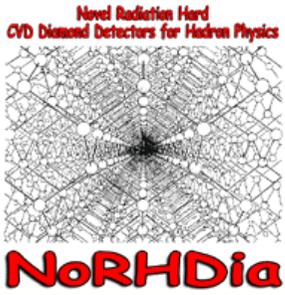


- not reproducible I-V for various samples

- asymmetry

bulk + surface current



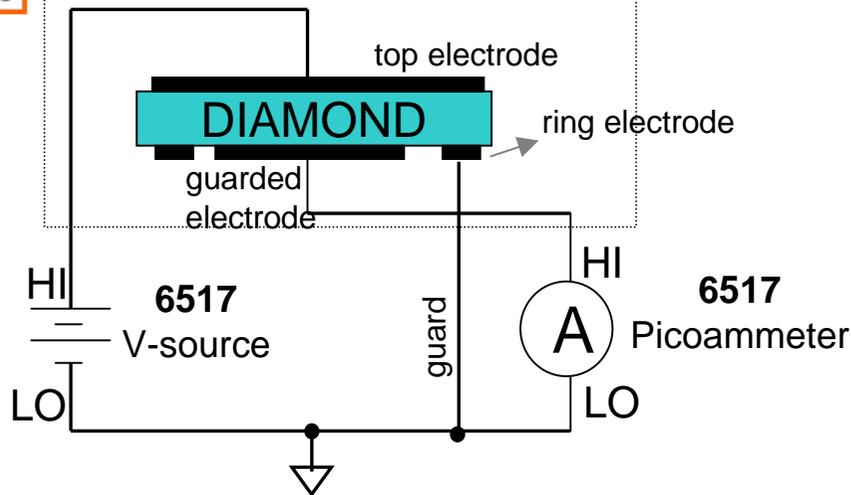


# CURRENT-VOLTAGE CHARACTERISTICS



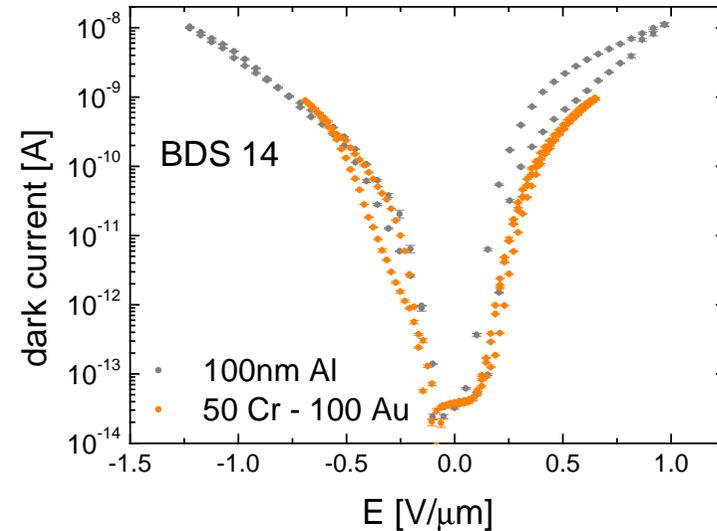
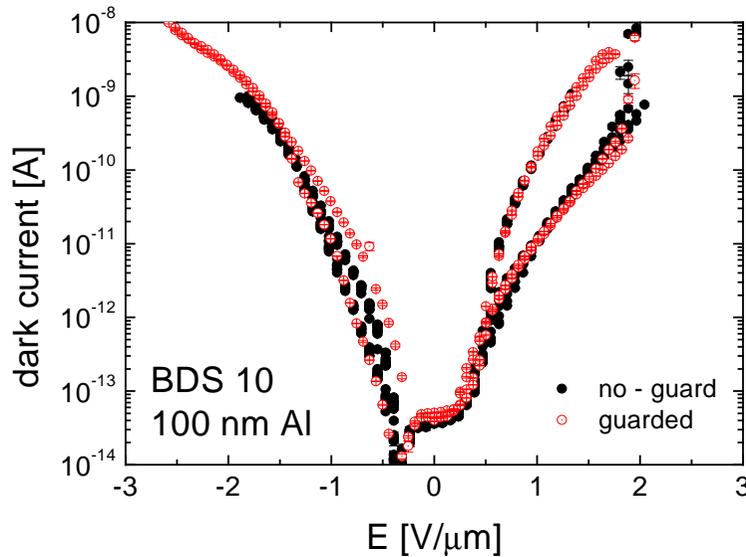
bulk current

screened box, no light + N<sub>2</sub> flow

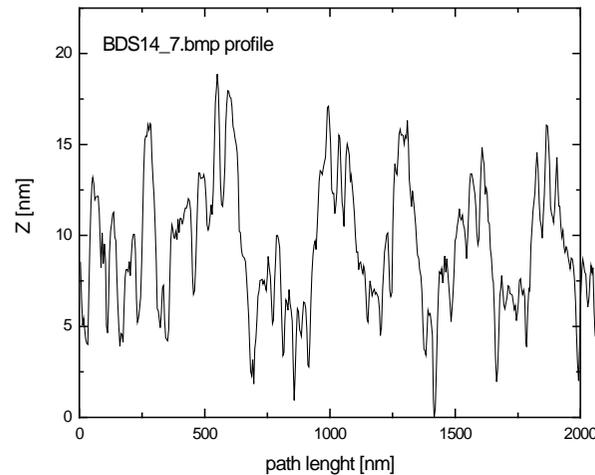
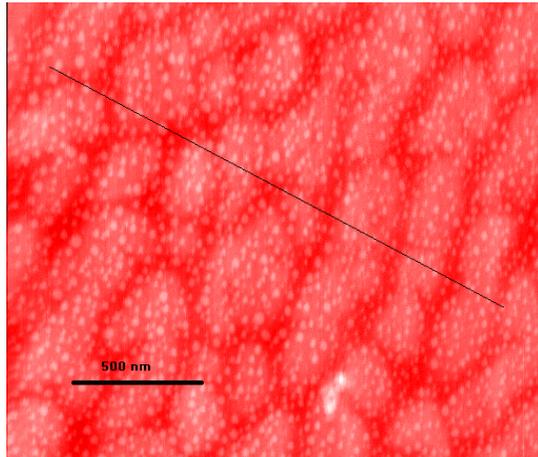


no difference in I-V for:

- various metallisation (Al,Cr,Ti) (2 samples tested)
- guarded electrode → mainly bulk leakage current (3 samples tested)

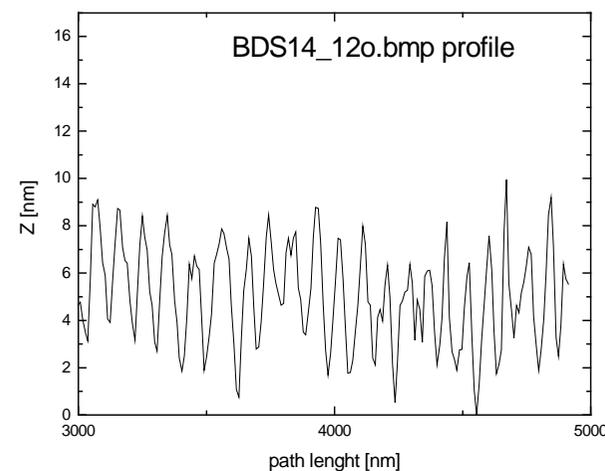


## AFM pictures of both diamond (BDS14) surfaces



substrate side (?)

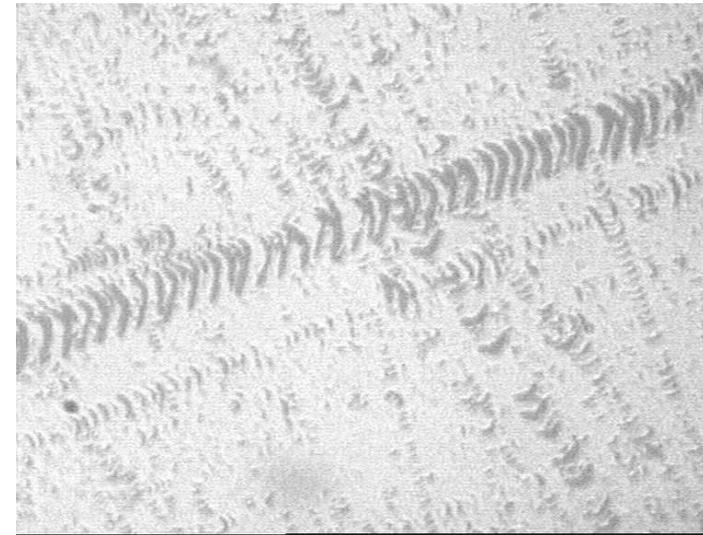
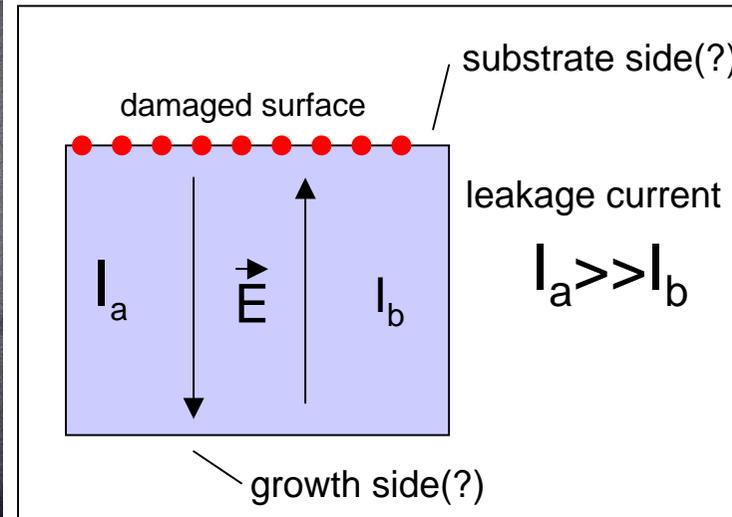
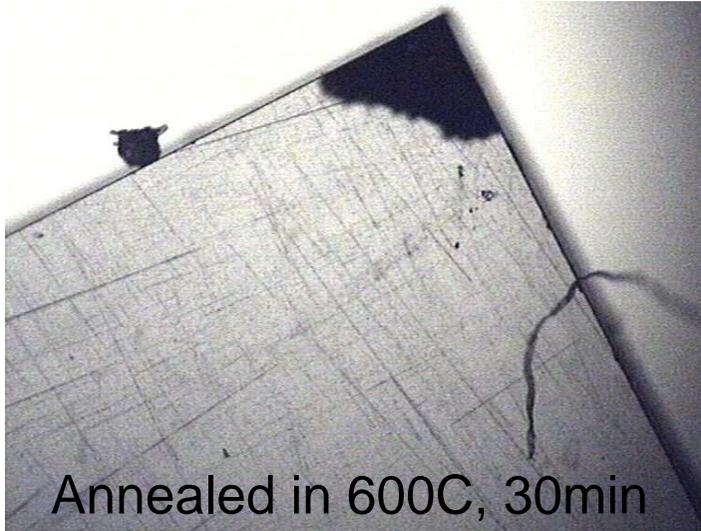
roughness  
rms  $\cong$  5.6 [nm]

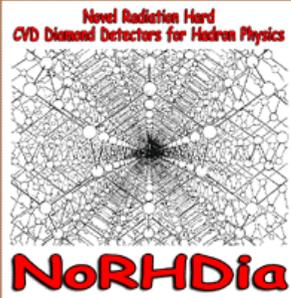


growth side (?)

roughness  
rms  $\cong$  1.4 [nm]

Asymmetry in I-V characteristic is present due to surface damage (polishing?) ... scratches „pop up” after samples annealing...

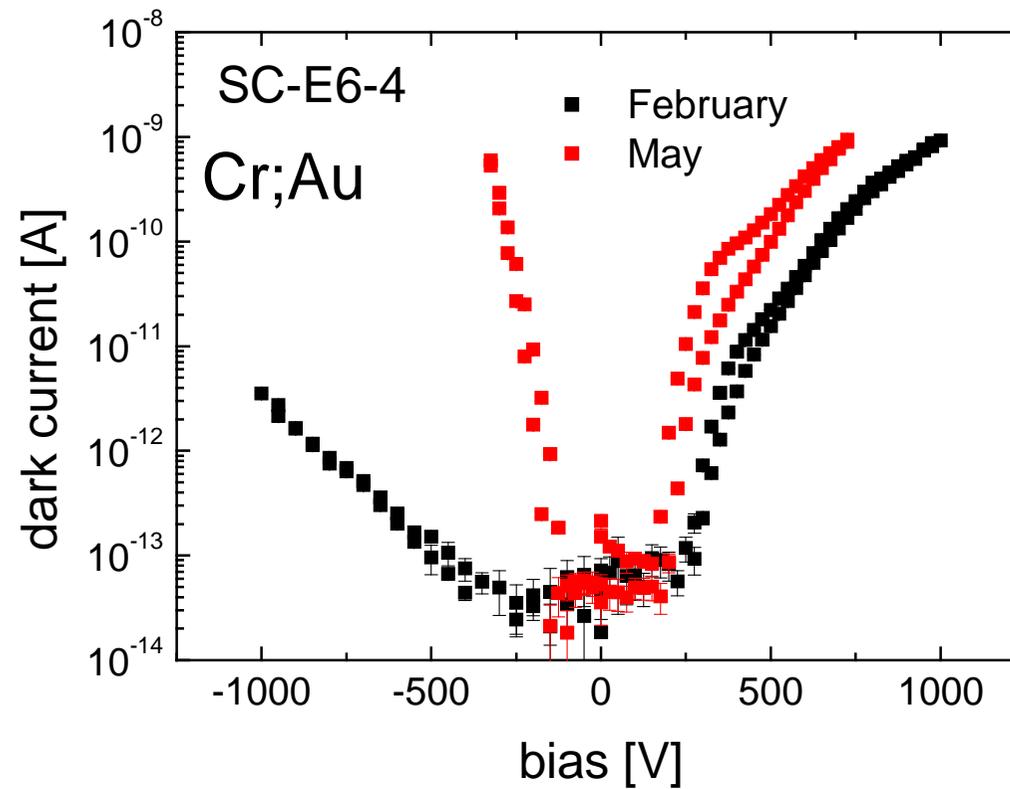


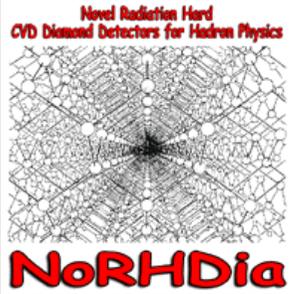


# CURRENT-VOLTAGE CHARACTERISTICS



## Long term stability

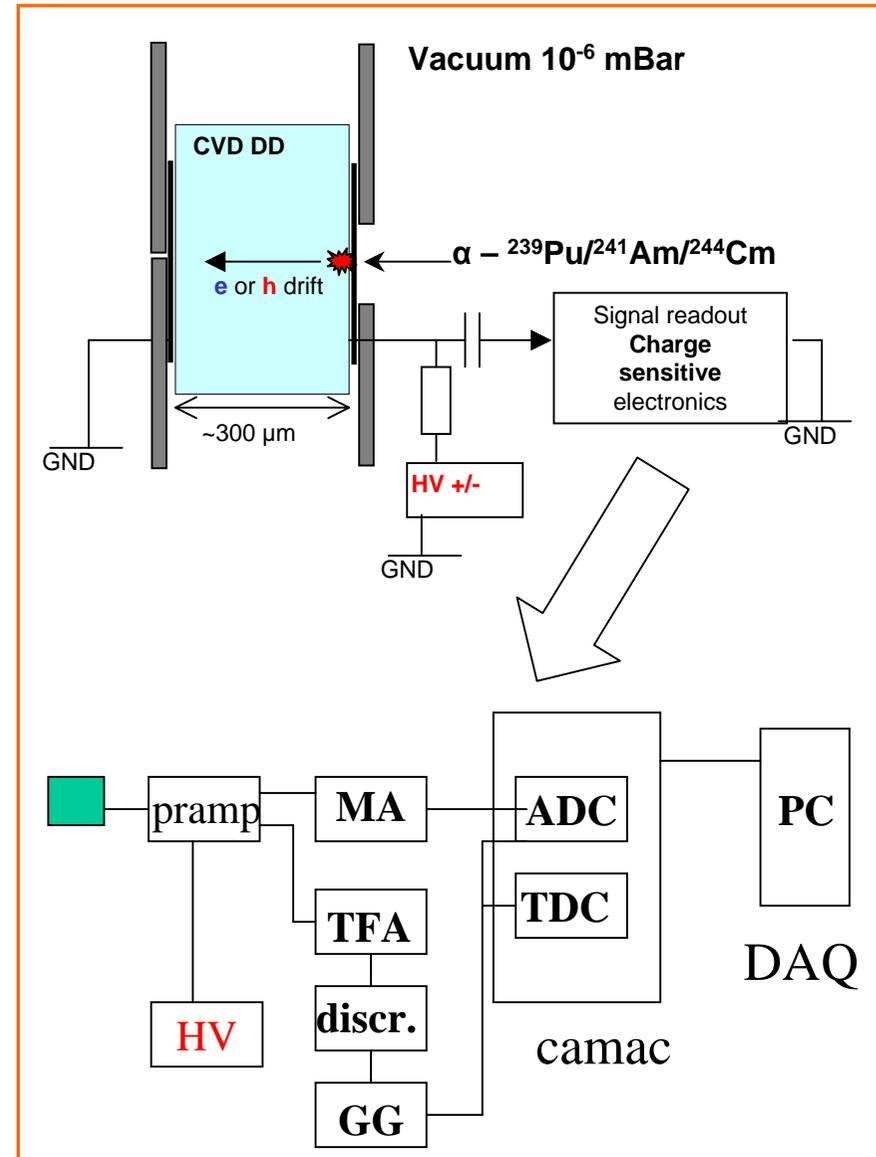


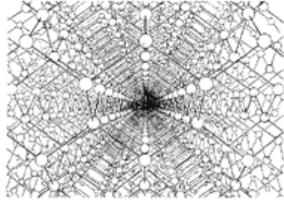


# CHARGE COLLECTION



- Use of an  $\alpha$ -source  $^{241}\text{Am}$  (5.486 MeV) for charge injection
- $\alpha$ -particle range in diamond  $\rightarrow \sim 12\mu\text{m}$
- detector thickness  $> 320\mu\text{m}$ , induced charge  $\rightarrow$  mainly motion of one type of carriers
- Choosing the HV +/-  $\rightarrow$  drift of holes or electrons
- presented geometry **+HV – holes drift, -HV - electrons drift**
- detector coupled to classical spectroscopy front-end electronic





# CHARGE COLLECTION

Saturation to ~ 68.6 [fC]  
for both  
electrons and holes drift.

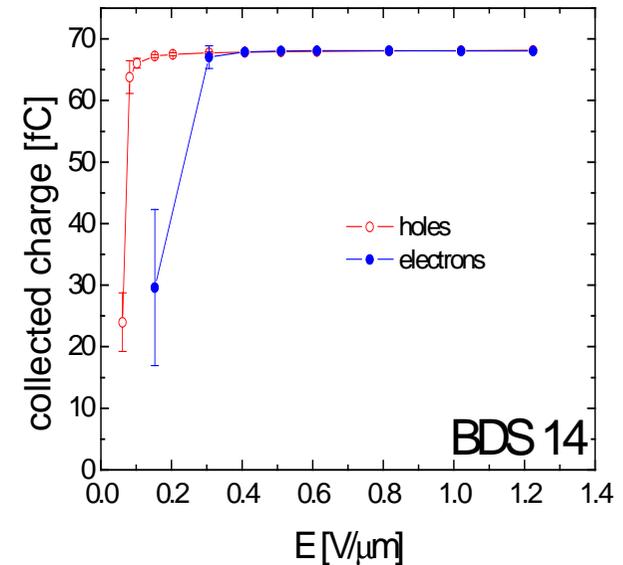
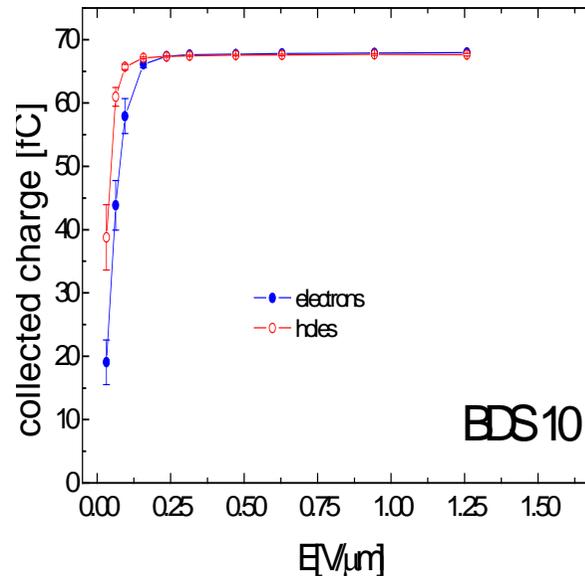
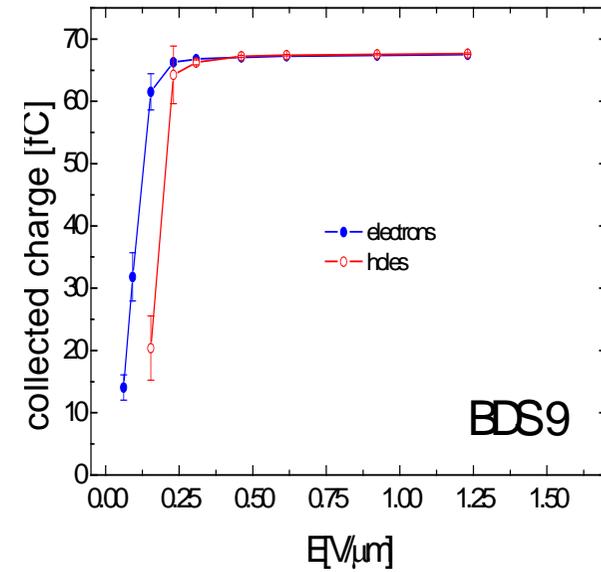
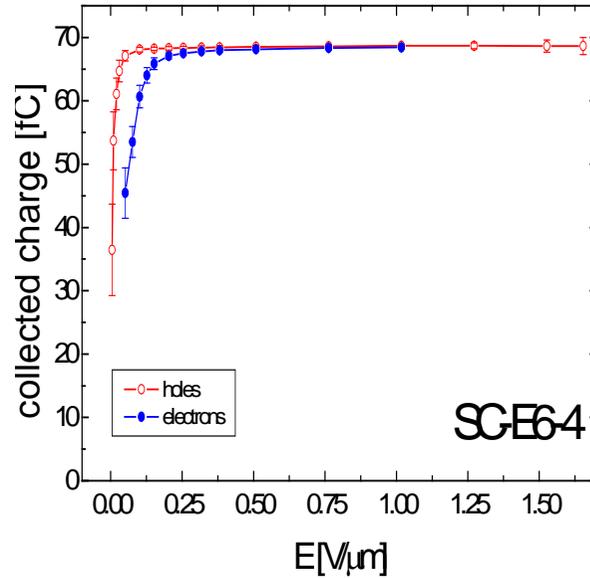


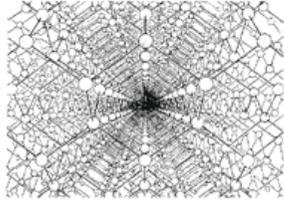
CCE=100% at low electric  
field < 0.3 V/mm



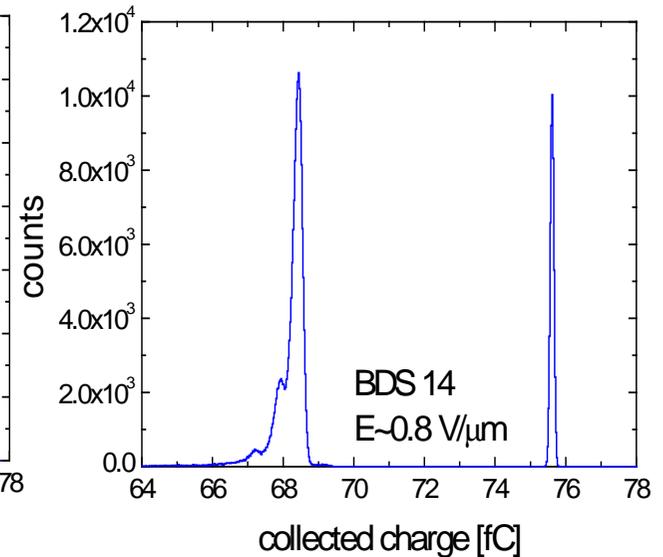
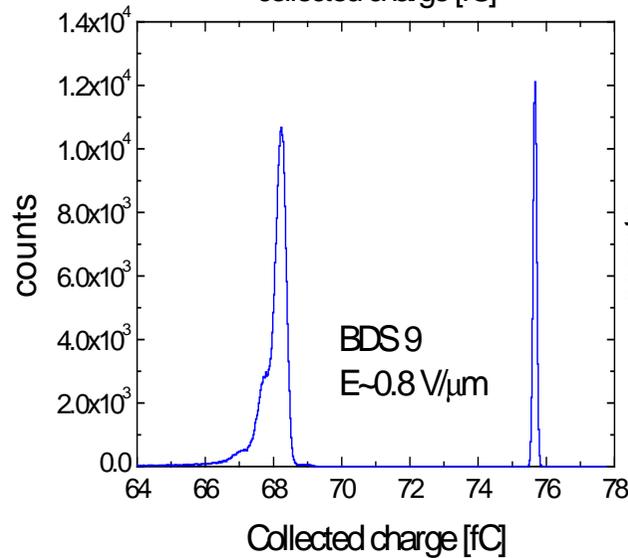
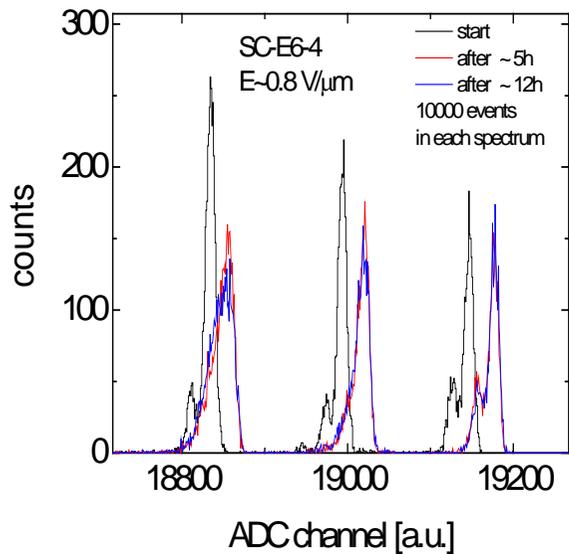
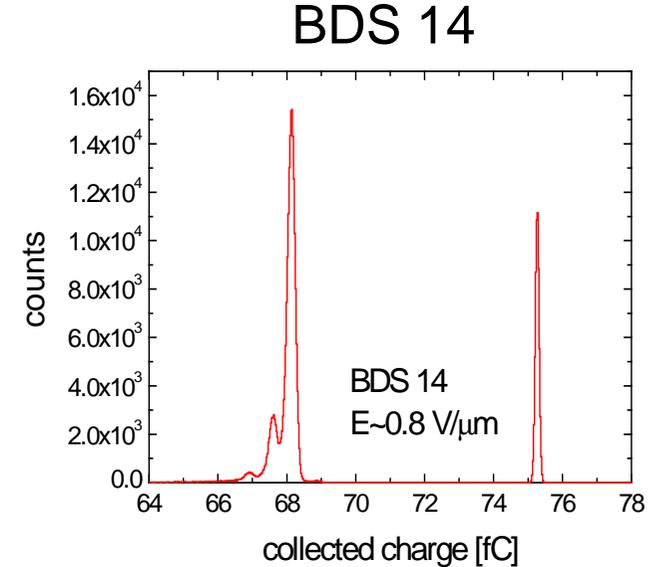
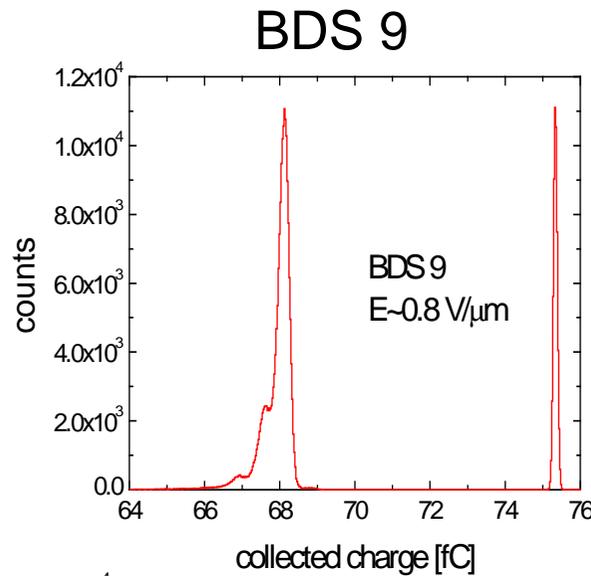
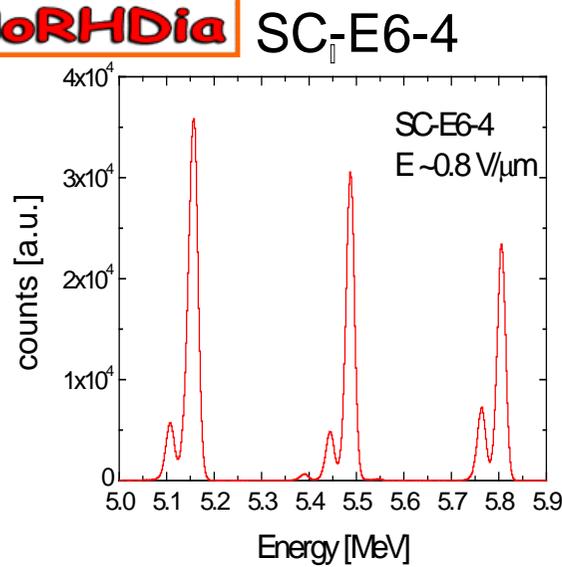
68.6 [fC] → 429 372 e-h

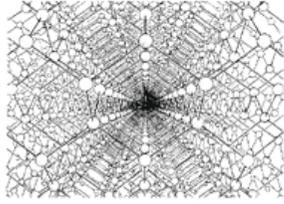
Average energy  
for e-h pair creation  
→ 12.8 eV/e-h





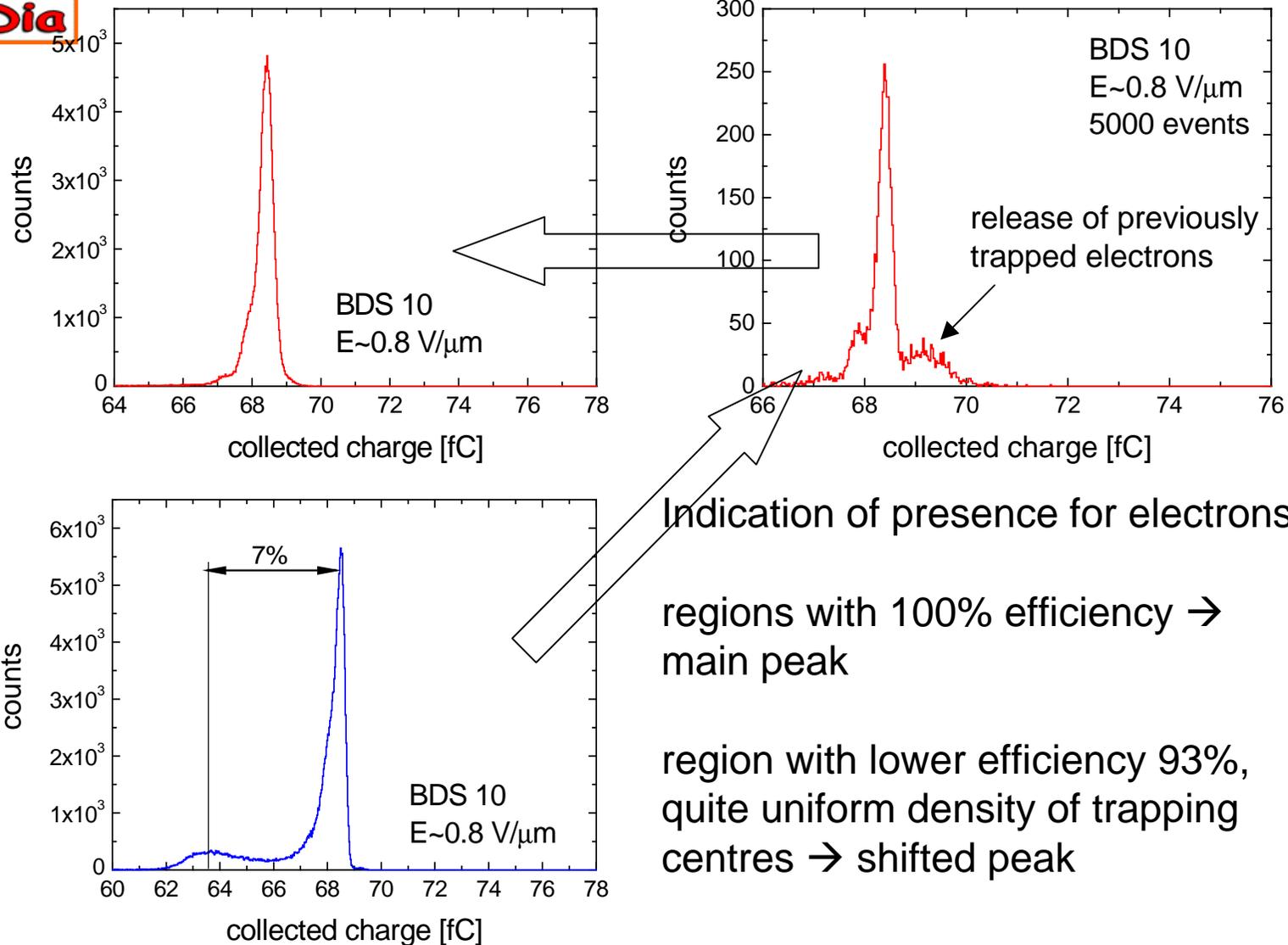
Time of spectrum collecting > 12h

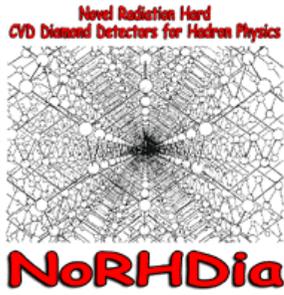




# DETECTION STABILITY

## BDS 10





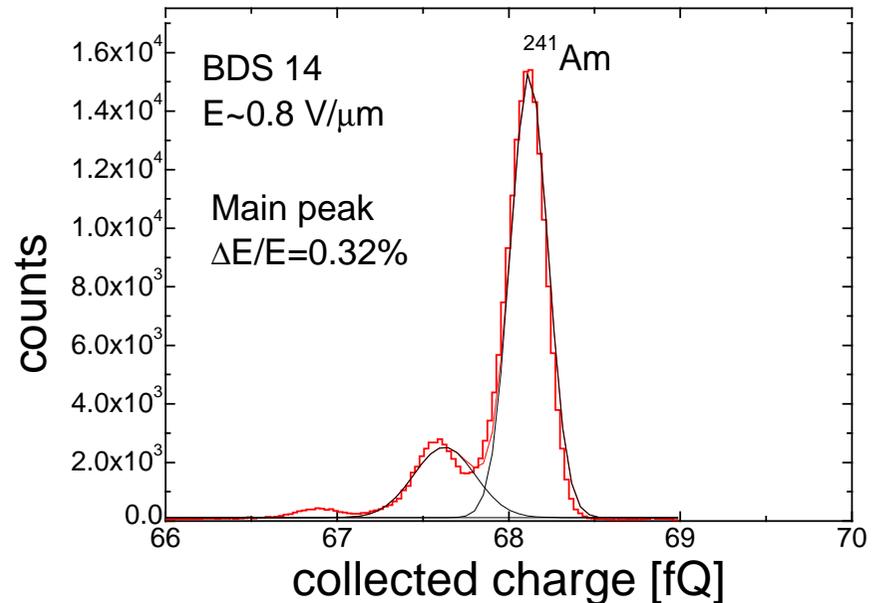
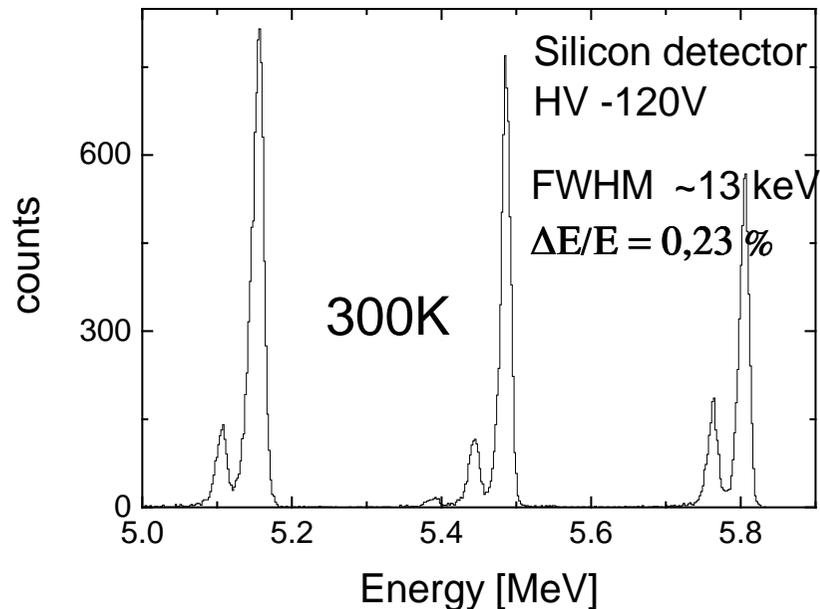
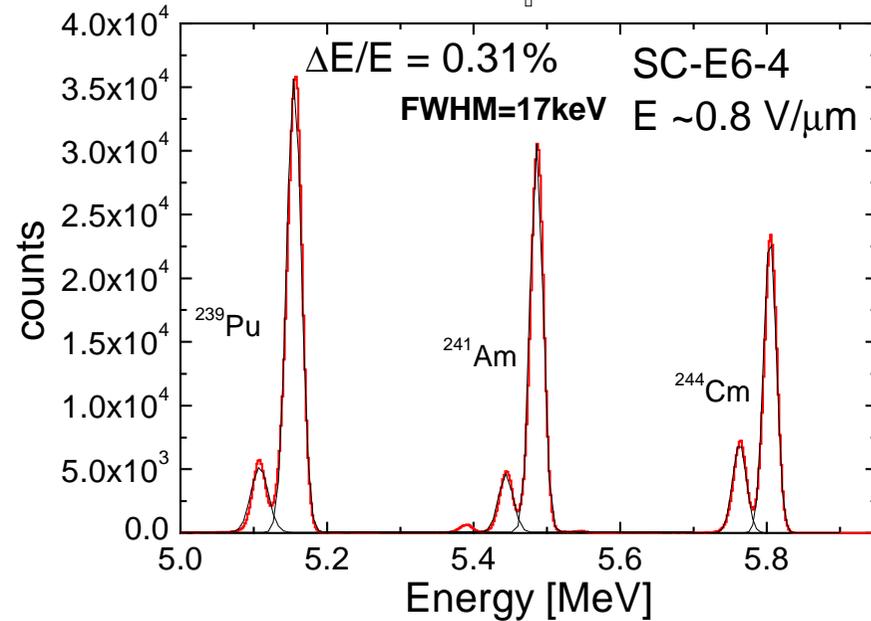
# ENERGY RESOLUTION

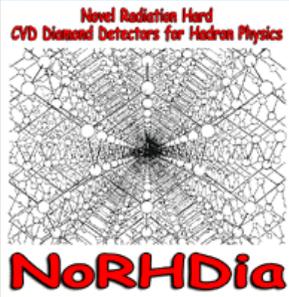


Diamond resolution close to silicon detectors:

**FWHM = 17 keV** (5.486 MeV) (sc-e6-4 holes)  
measured with not dedicated CS electronics

silicon  $\rightarrow$   $e \sim 3.6$  eV/e-h; diamond  $\rightarrow$   $e \sim 12.8$  eV/e-h  
We are close to statistical limits (Fano factor?)





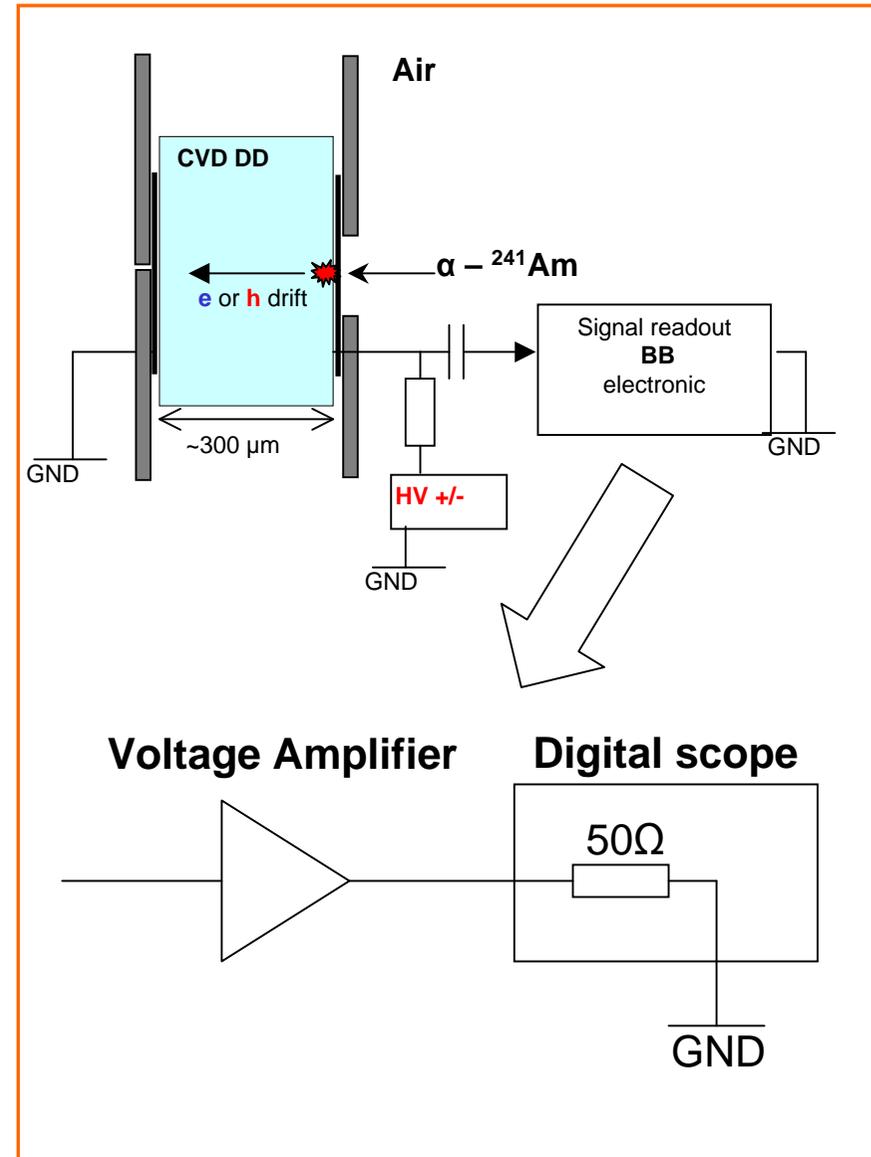
# TIMING PROPERTIES

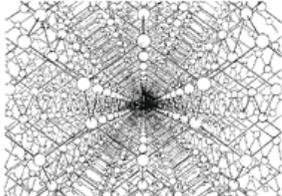


## Time of Flight Technique

**Low impedance of 50  $\Omega$  voltage amplifier**  
DBA – II, bandwidth **2.3 GHz** (3dB), gain 44dB

**Digital Scope**  
bandwidth **3GHz**, 20GS/s

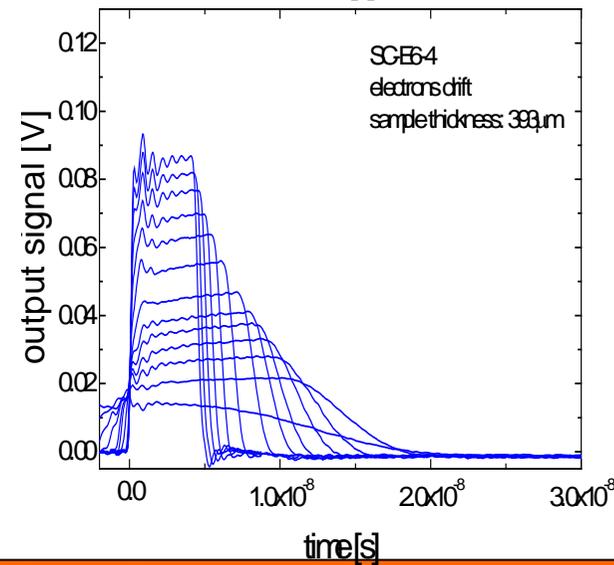
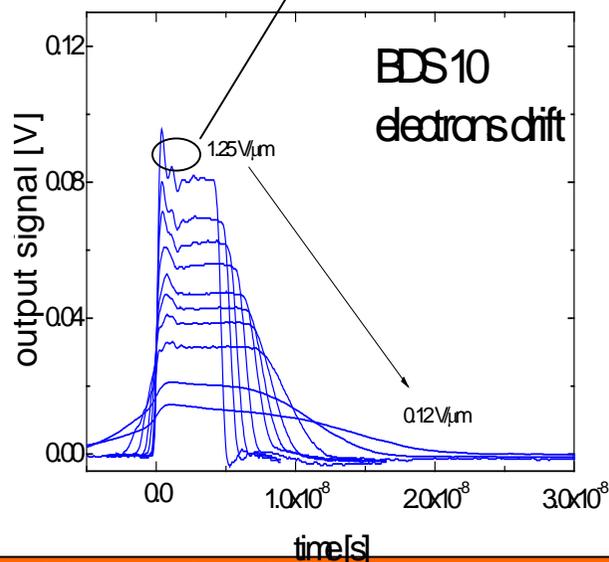
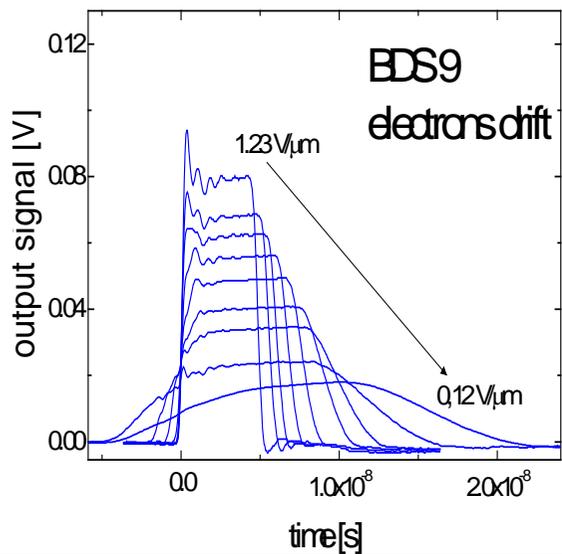
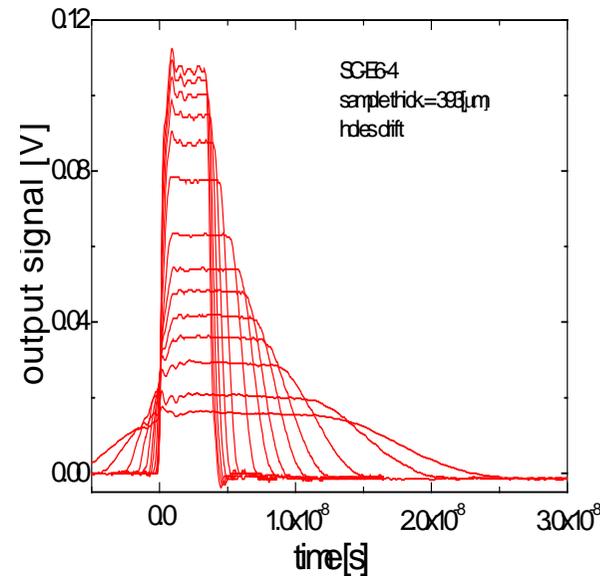
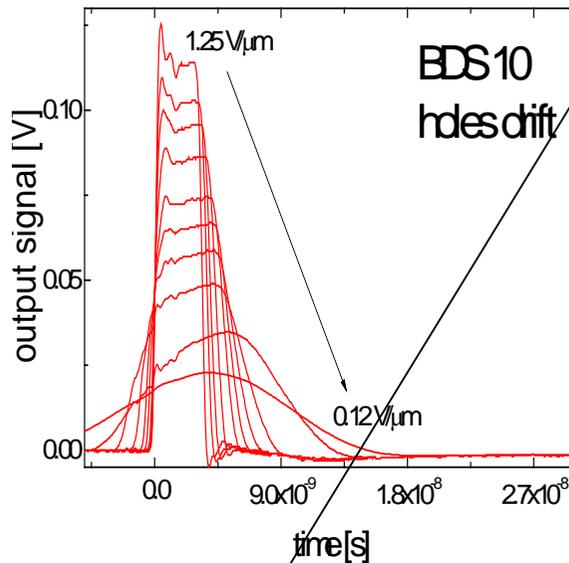
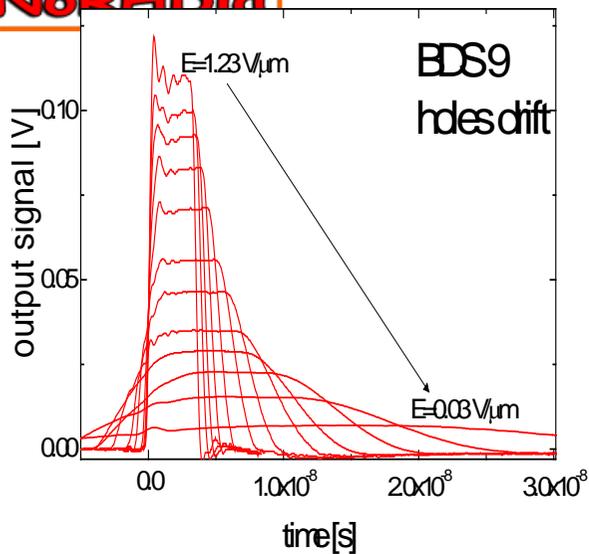


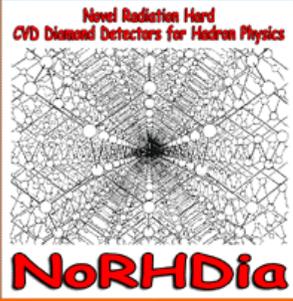


# TIMING PROPERTIES

Average signals from 500 single shots

electronics oscillation 2GHz  
due to 50ohm mismatching





# TIMING PROPERTIES



## electron drift signals

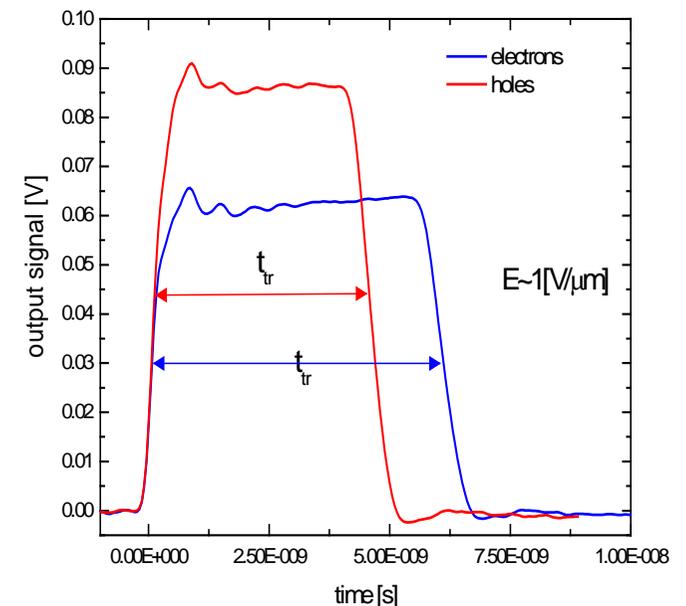
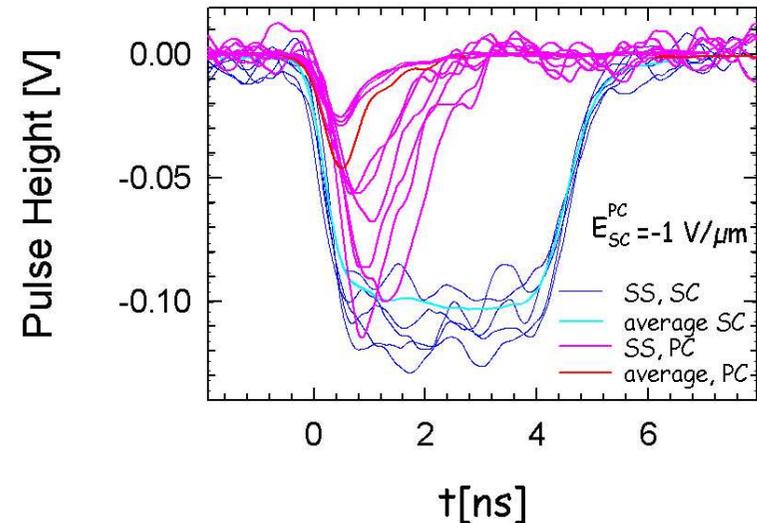
Assuming uniform internal electric field (flat top of BB signals) and CCE=100%

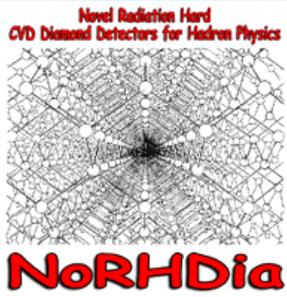
$$v_{dr}(E) = \frac{d}{t_{tr}}$$

$d$  – detector thickness

$t_{tr}$  – transition time → FWHM of BB signals

error → standard deviation of signals at FWHM

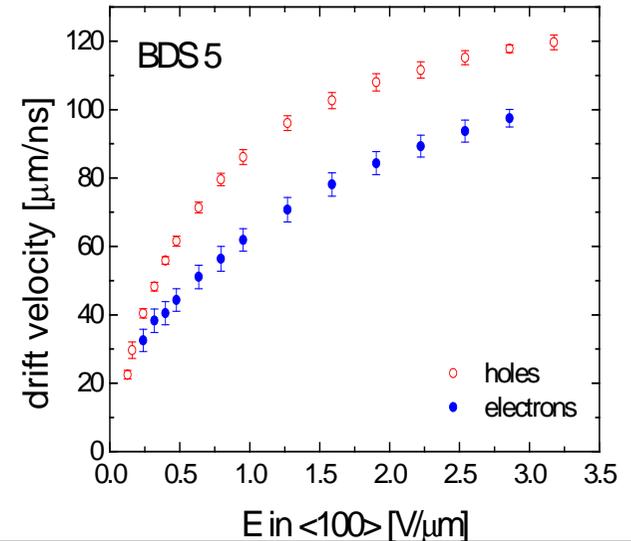
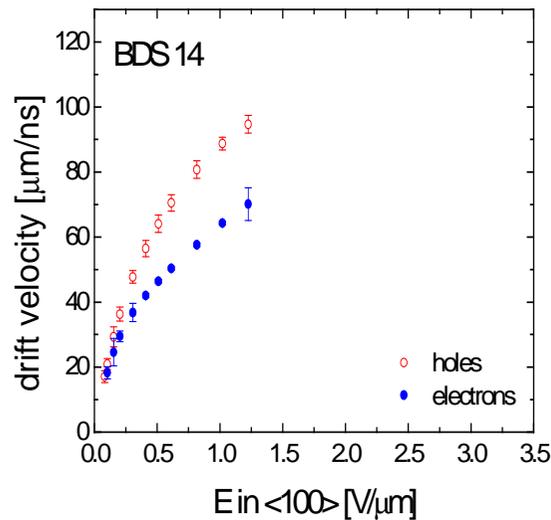
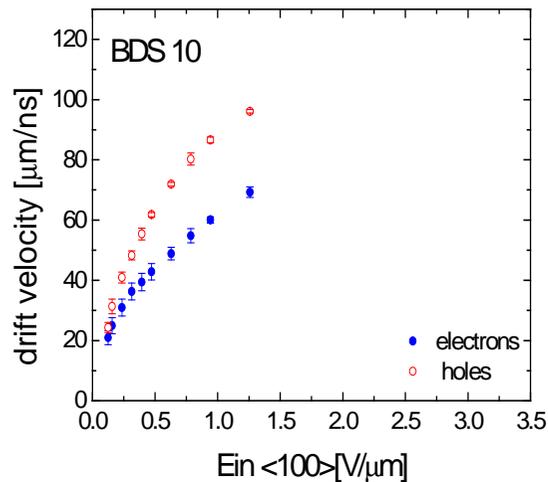
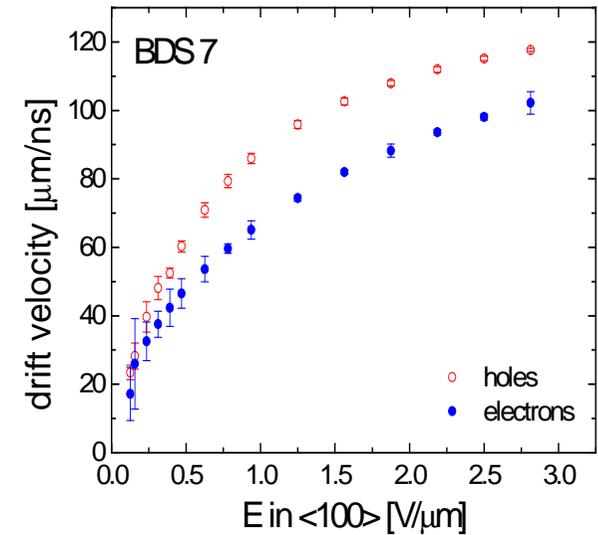
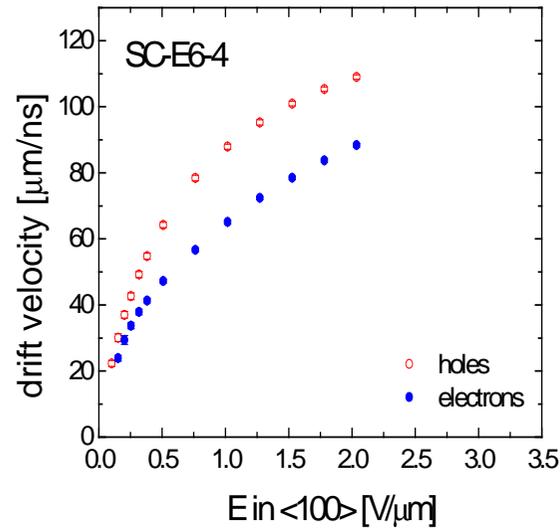
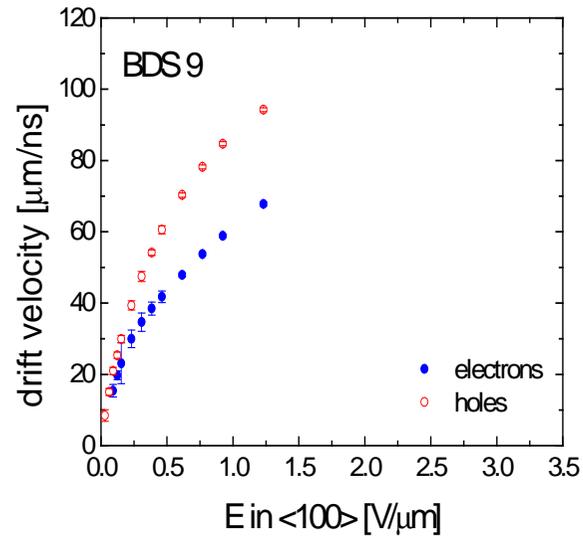


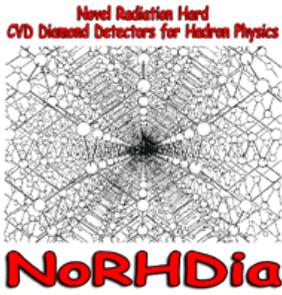


# TIMING PROPERTIES



## Drift velocities for **electrons** and **holes**





# TIMING PROPERTIES

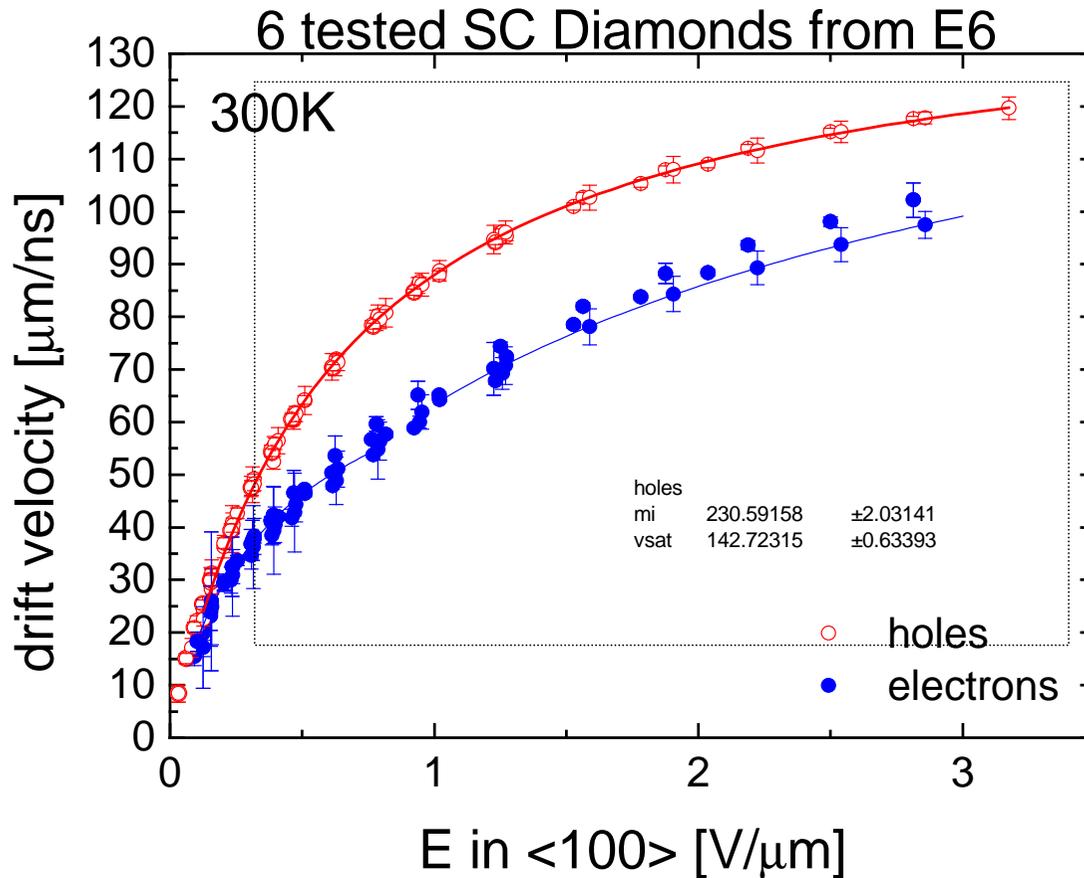


$$V_{dr} = \frac{\mu_0 \cdot E}{\left[1 + \left(\frac{v_{sat} \cdot E}{\mu_0}\right)^\beta\right]^{1/\beta}}$$

$\xrightarrow[\beta \approx 1]{\text{holes}}$ 
 $V_{dr} = \frac{\mu_0 \cdot E}{1 + \frac{v_{sat} \cdot E}{\mu}}$

$\xrightarrow{\text{electrons}}$

**2 fits:**  
 0.3 – 1 V/μm → μ<sub>0</sub>  
 1 – 3 V/μm → v<sub>sat</sub>



**Holes**

μ<sub>0</sub> ≅ **2332 [cm<sup>2</sup>/Vs]**

v<sub>sat</sub> ≅ **140 [μm/ns]**

**electrons**

μ<sub>0</sub> ≅ **1400 - 3100 [cm<sup>2</sup>/Vs]**

v<sub>sat</sub> ≅ **190 [μm/ns]**



### Current voltage characteristics

- huge difference in leakage current for various samples
- no difference for guarded samples → mainly bulk leakage
- Asymmetry in I-V probably due to damaged surface as a result of samples polishing → requires overgrowth after polishing
- No difference for various metallisation → proposal to use light elements e.g. Al



### charge collection, stability, and $\Delta E$

- CCE ~ 100% at low  $E < 0.3\text{V}/\mu$  for holes and electrons – most of tested samples
- all samples  $\rightarrow$  “spectroscopic grade” some of them resolution close to silicon detectors
- perfect behavior for holes drift – no trapping (or negligible)
- most of them stable as well for electrons drift



## Timing properties

- flat top of BB signals for all tested samples – uniform internal electric field – no internal space charge
- common behavior -->
  - holes drift velocity  $>$  electrons drift velocity in  $\langle 100 \rangle$
- intrinsic limit for timing application with CSA electronic drift of electrons 1 ns / 100  $\mu\text{m}$  (optimistic  $E=2.8\text{V}/\mu\text{m}$ )
- uniform rise time of  $\sim 160$  ps (limited by electronics) jitter - 26 ps for BB electronic